

PAT-NO: JP355088332A
DOCUMENT-IDENTIFIER: JP 55088332 A
TITLE: METHOD OF MASK ALIGNMENT
PUBN-DATE: July 4, 1980

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APPL-NO: JP53163175

APPL-DATE: December 26, 1978

INT-CL (IPC): H01L021/30

US-CL-CURRENT: 33/533

ABSTRACT:

PURPOSE: To set accurately a gap between a substrate and a mask without touching by a method wherein a distance between the mask and the substrate is detected on a gap measuring apparatus provided on substrate side, and the detected distance is transferred to a gap measuring apparatus provided on mask side.

CONSTITUTION: A plural gap measuring apparatus 7 is enclosed in a substrate base 6. Next, a reference plate 3 is placed on the substrate base 6, the distance is measured and then the gap measuring apparatus 7

is zeroed. Then, the reference plate 3 is demounted, a mask 1 is brought near to the substrate 6, and a gap between a reference plane 8 and the substrate base 6 is measured. The measured value is set as an initial value of a gap measuring apparatus 10 on mask side. After that, a mask holder 9 is kept apart from the substrate base 6. Next, a wafer with a resist applied thereon is placed on the substrate base 6. Then, the mask holder 9 is moved to come near to the substrate base 6, a gap to the substrate base 6 is measured on the gap measuring apparatus 10 until a given value is obtained.

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